

# Leveraging Simulation in MEMS Development

Coventor Workshop | Woburn, MA

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AMFITZGERALD  
& ASSOCIATES

# Overview

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- **About AMFitzgerald**
- **Why is MEMS development still so hard?**
- **Value of simulation**
- **Leveraging simulation – practical tips**
- **Closing remarks**

# Mission

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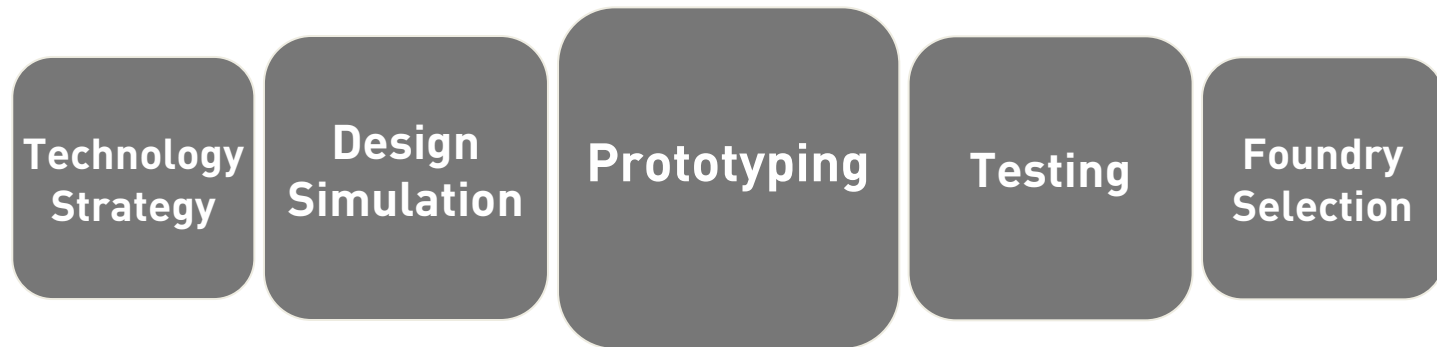


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**We turn your ideas into silicon.**

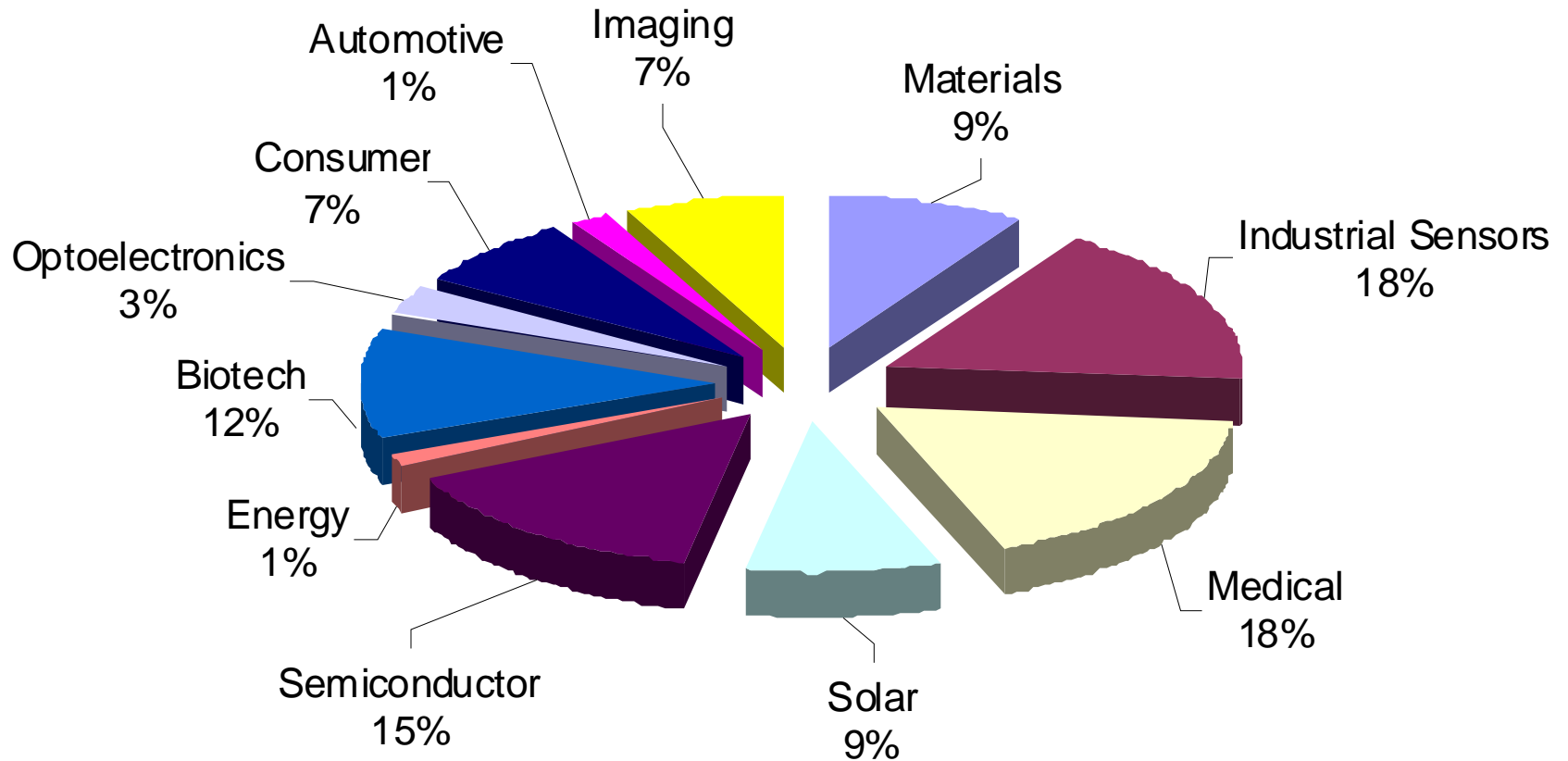
# Fully integrated services: concept to foundry

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- Complete design and project management
- Feasibility and cost analysis
- Design optimization using simulation
- Process development on 150 mm wafers
  - Prototype fabrication with own staff engineers at UC Berkeley's Microlab
- Test system development
- Packaging, system integration
- Technology transfer to foundries for production

# Our diverse customer base



# MEMS design and prototyping expertise

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## Technologies we have developed:

- **Piezoresistive sensors**
- **Piezoelectric (AlN and ZnO) sensors**
- **Capacitive sensors**
- **Electrostatic actuators**
- **Micro-cantilevers**
- **Microfluidics**
- **Mold masters**
- **Gratings and lenses (x-ray, optical, acoustic)**
- **Solar cells**

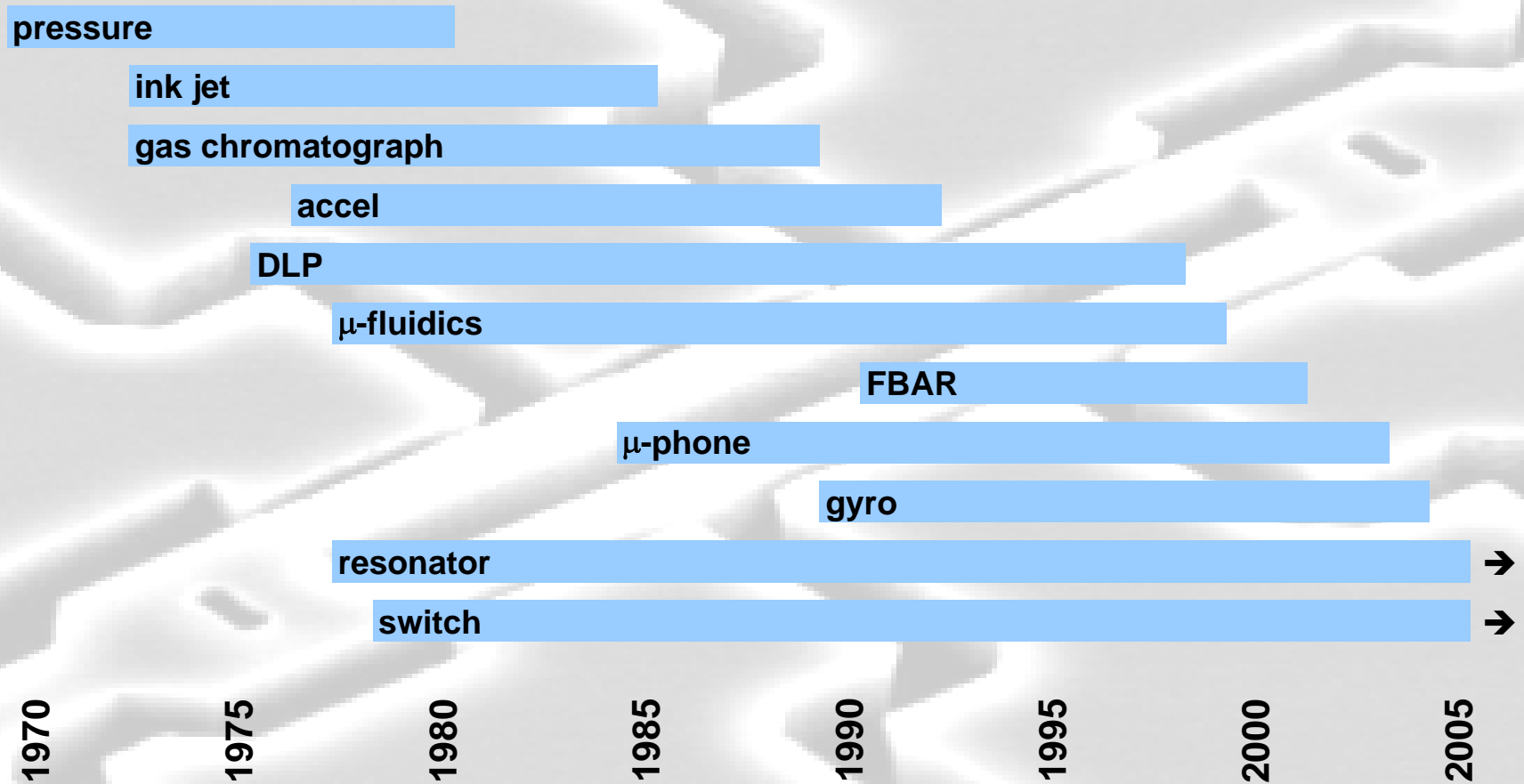
***Over 70 clients served***

## Application areas:

- **Consumer electronics**
- **Medical implant**
- **Medical diagnostics**
- **Infrared imaging**
- **Industrial safety**
- **System health monitoring**
- **Ultrasound imaging**
- **Optical telecom**
- **Solid state lasers**
- **Chip cooling**
- **Cell culture**
- **Drug discovery**
- **Gas flow metering**
- **Advanced packaging**
- **Solar**

**Why is MEMS development still so hard?**

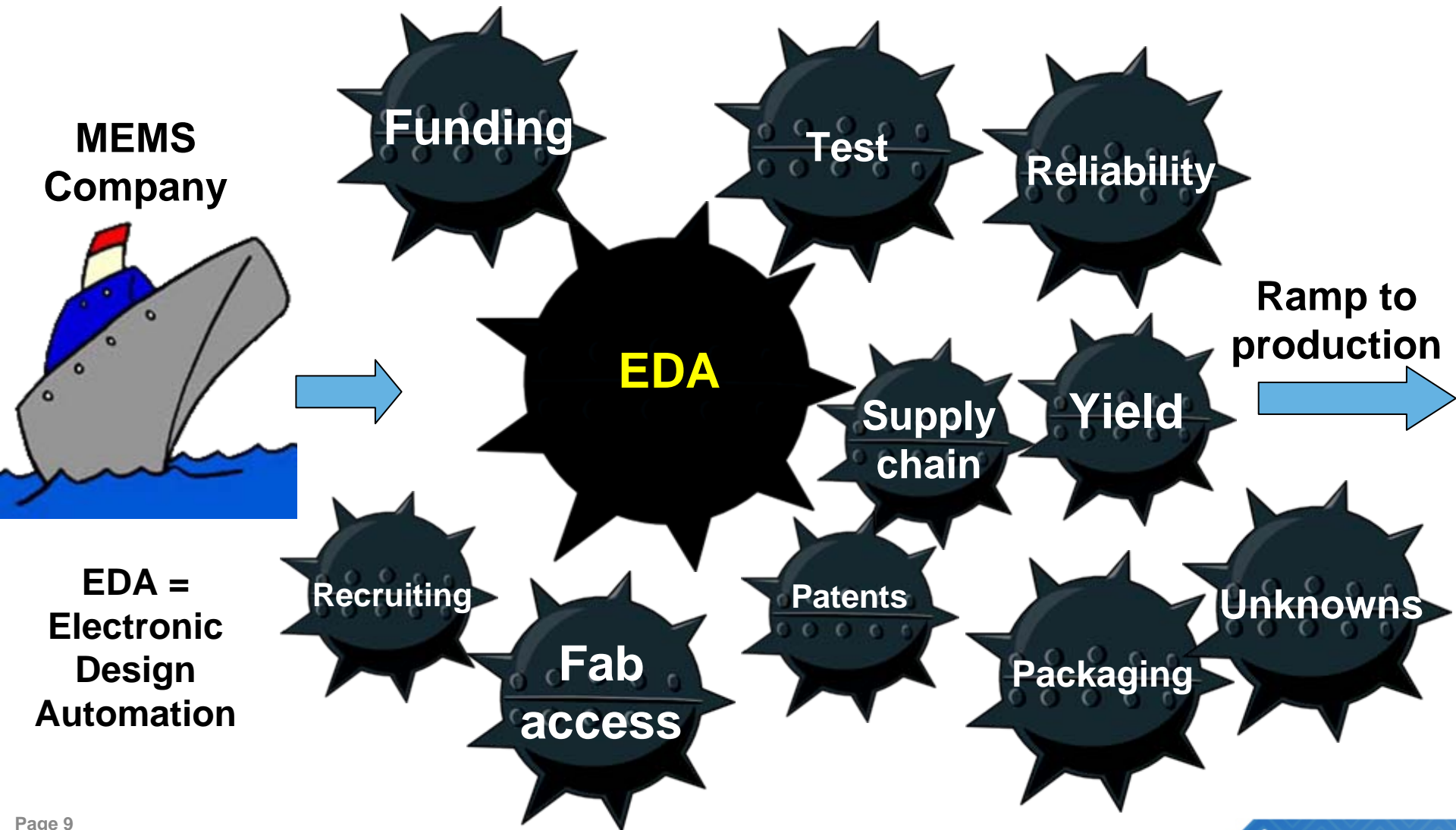
# MEMS R&D Cycles





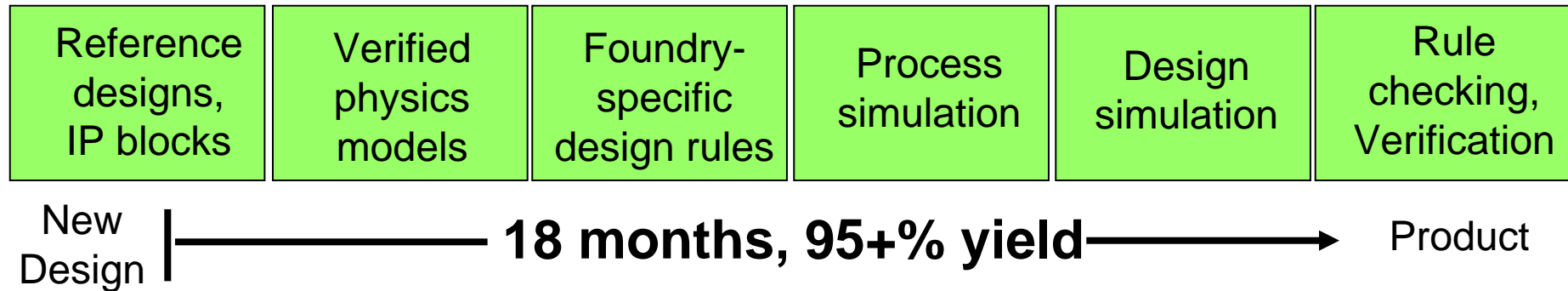
# The perilous MEMS development journey (early stage)

Millions of dollars, years and many casualties

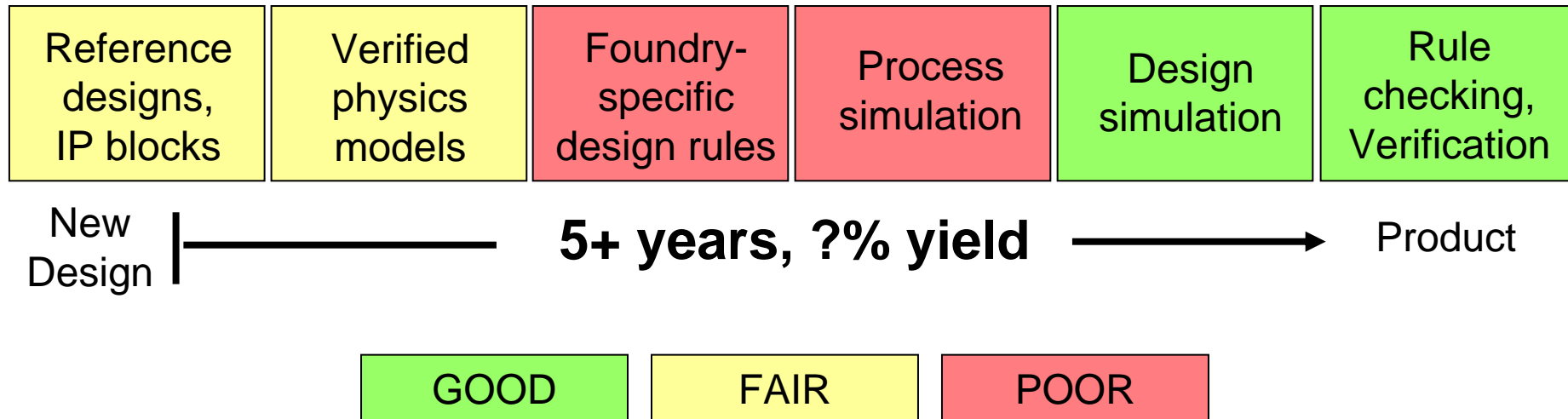


# Lack of integrated EDA forces multiple design-fab-test cycles

## Semiconductor EDA



## MEMS Industry EDA



# MEMS industry must work to close these gaps

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Reference  
designs,  
IP blocks

Only established MEMS companies have these (proprietary) – a major advantage

Verified  
physics  
models

Stiction, electrostatic charging, fracture, time-dependent material behavior

Foundry-  
specific  
design rules

Rules to prevent unfeasible or marginal designs

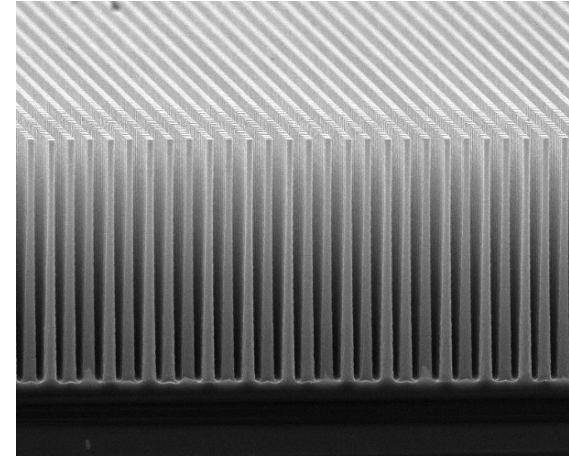
Process  
simulation

Understanding how process affects mechanical performance

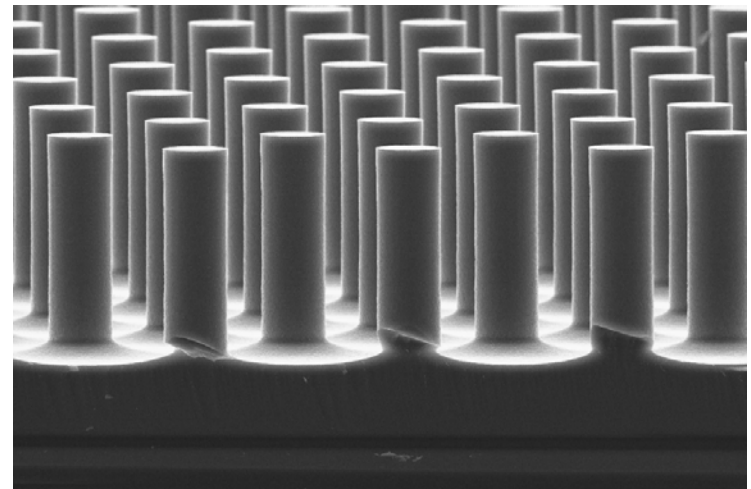
## Rules to prevent unfeasible designs

- **MEMS PDKs needed – Process Design Kit**
  - What features can be robustly manufactured?
- **Examples of process/feature design rules:**
  - Feature size resolution
  - Step coverage geometry
  - Pattern load factor allowed (% of wafer being etched)
  - Process module sequencing
    - No litho after deep etch

2 um pillar, 20:1 aspect ratio



High load factor etch

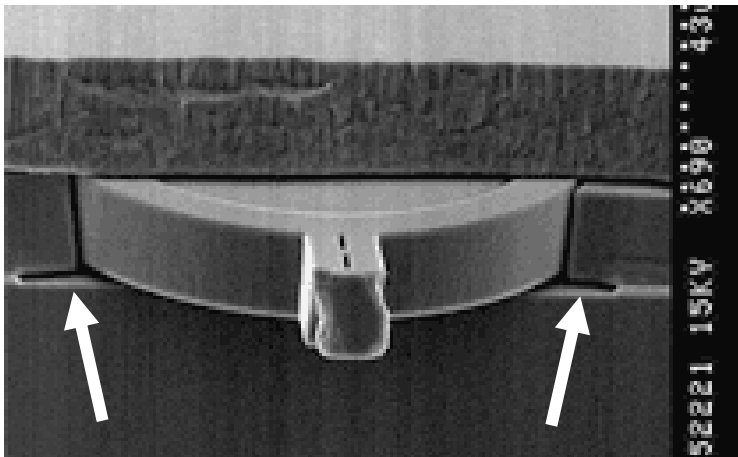


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# Process affects mechanical performance

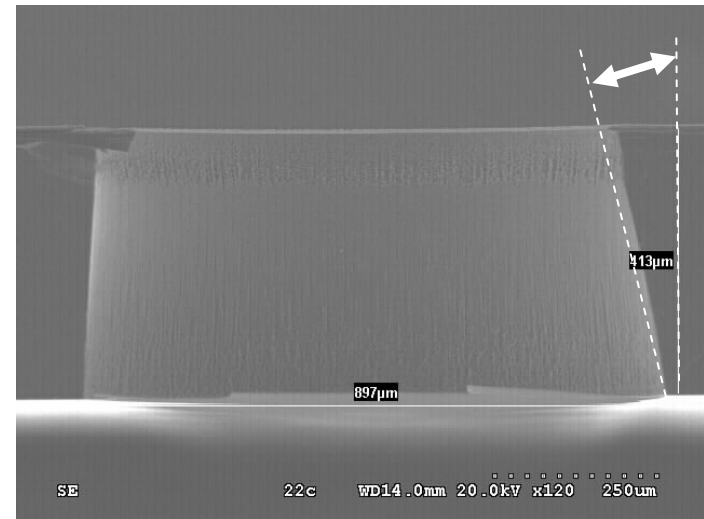
- **Lateral undercutting (boundary conditions)**
  - Resonant structures greatly affected
- **Thermal budget (film stresses)**
- **DRIE etch sidewall (geometry)**
  - Critical to inertial sensor performance

Undercut during sacrificial release



Chipworks, SiTime

DRIE sidewall taper in large open area



Tegal

# Lack of integrated EDA hurts the entire industry

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- **Time to market suffers badly**
  - Impaired ability to reach new markets
  - Opportunity cost
- **Under-utilization of simulation leads to wasted time and money in the fab**
  - More on this in a minute!
- **Escalating, unknowable development costs**
  - Soured investors, premature death of companies

# **The value of simulation**



# If you were lost in the wilderness...

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If you had a GPS unit, it would be easy to get home



With some effort, you could find your way with a compass



But you wouldn't just start wandering around, would you?





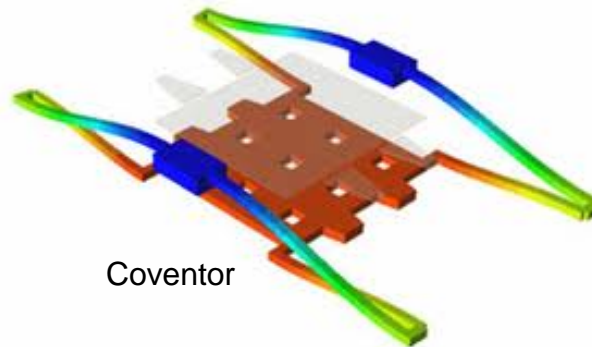
# MEMS development often gets lost in the wilderness

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We don't have a perfect EDA system to give us all the answers

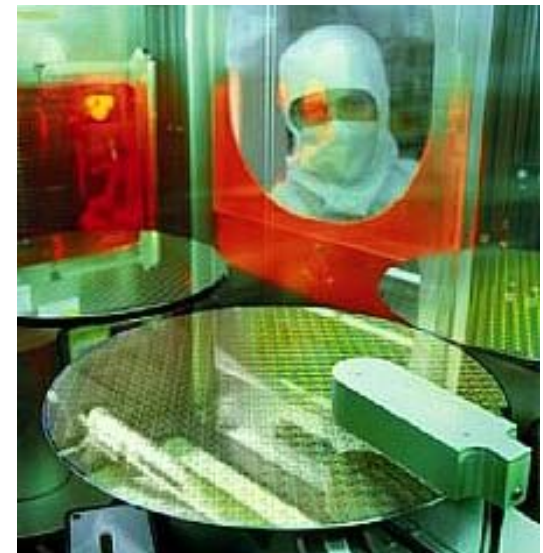


Simulation can't tell us everything, so why bother?



Coventor

We're fab guys - let's just build it and see what happens.



# Top excuses for avoiding simulation

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1. **“The software is too expensive”**
2. **“I don’t trust the results” (= I don’t understand how to use the software properly)**
3. **“We don’t know our material properties”**
4. **“We need to build prototypes anyway”**
5. **“We can figure it out by doing lots of design variants” (Design of Experiments)**
6. **“We tried, but we could never get the model to match reality”**

# It's slow and expensive to “just build it”!

- **Bare minimum costs for a development batch of ten 150 mm wafers (recurring costs only)**

6 layer MEMS process

Burdened labor rate \$100/hr.

Fab cost per layer (mask+fab)      \$15K, 1 week

	<u>Man-hours</u>	<u>Cost</u>	<u>Time, weeks</u>
Mask layout and checking	160	\$ 16,000	2
Fab cost		\$ 90,000	6
Test and measurement	80	\$ 8,000	1
<b>Total</b>		<b>\$ 114,000</b>	<b>9</b>

**How many design-fab-test  
cycles can you afford?**

# The tools we have are much better than nothing

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Take the time to learn how to use it properly. It could save your company.



## Leveraging simulation – practical tips



# Typical challenges in simulation of MEMS

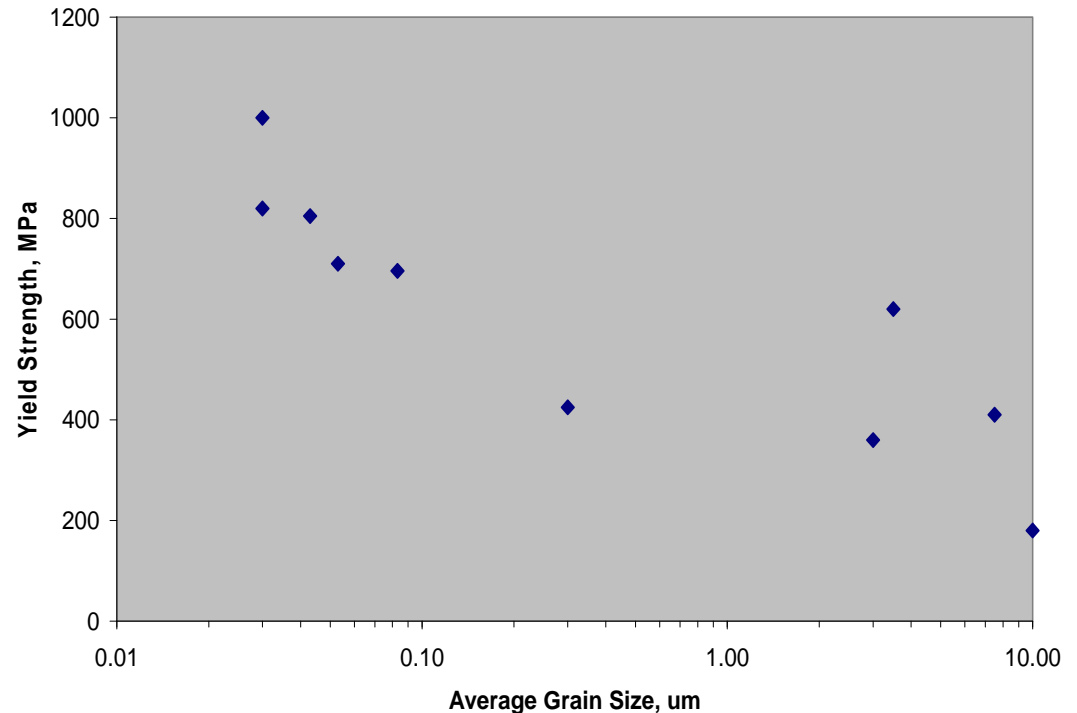
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- **Materials properties uncertainty**
  - Thin film properties
  - Non-linear behavior
- **Boundary conditions**
- **Load limits for brittle structures**
  
- **You can work around these – with some effort – and reap the benefits of simulation**

# Problem: Materials properties of thin films

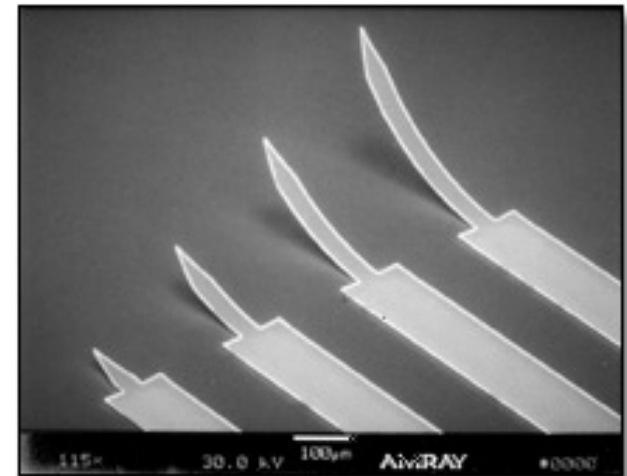
- Recipe dependent
- Tool to tool variation

Figure 1: Correlation of Grain Size with Tensile Strength of Electroplated Nickel

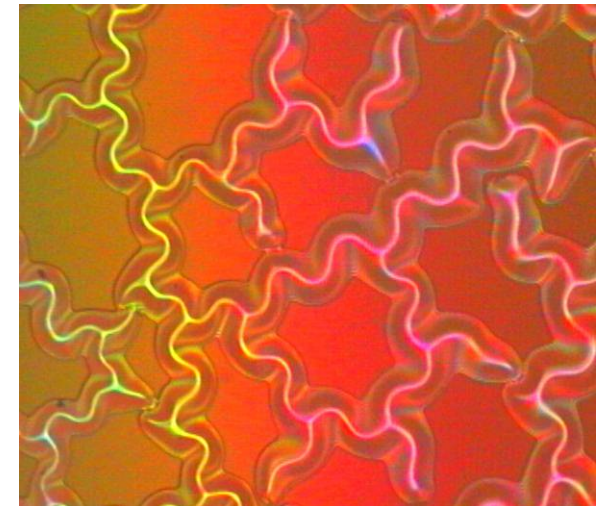


# Problem: Residual stress in thin films

- **Stress due to CTE mismatch and/or intrinsic to material**
  - Metals typically tensile
  - Oxides always compressive
  - *Stress can change with thermal budget*
- **Released structures are affected: beams, membranes**
  - Bowing, buckling
  - Cracking
  - Frequency shifts



parc's StressedMetal AFM tips

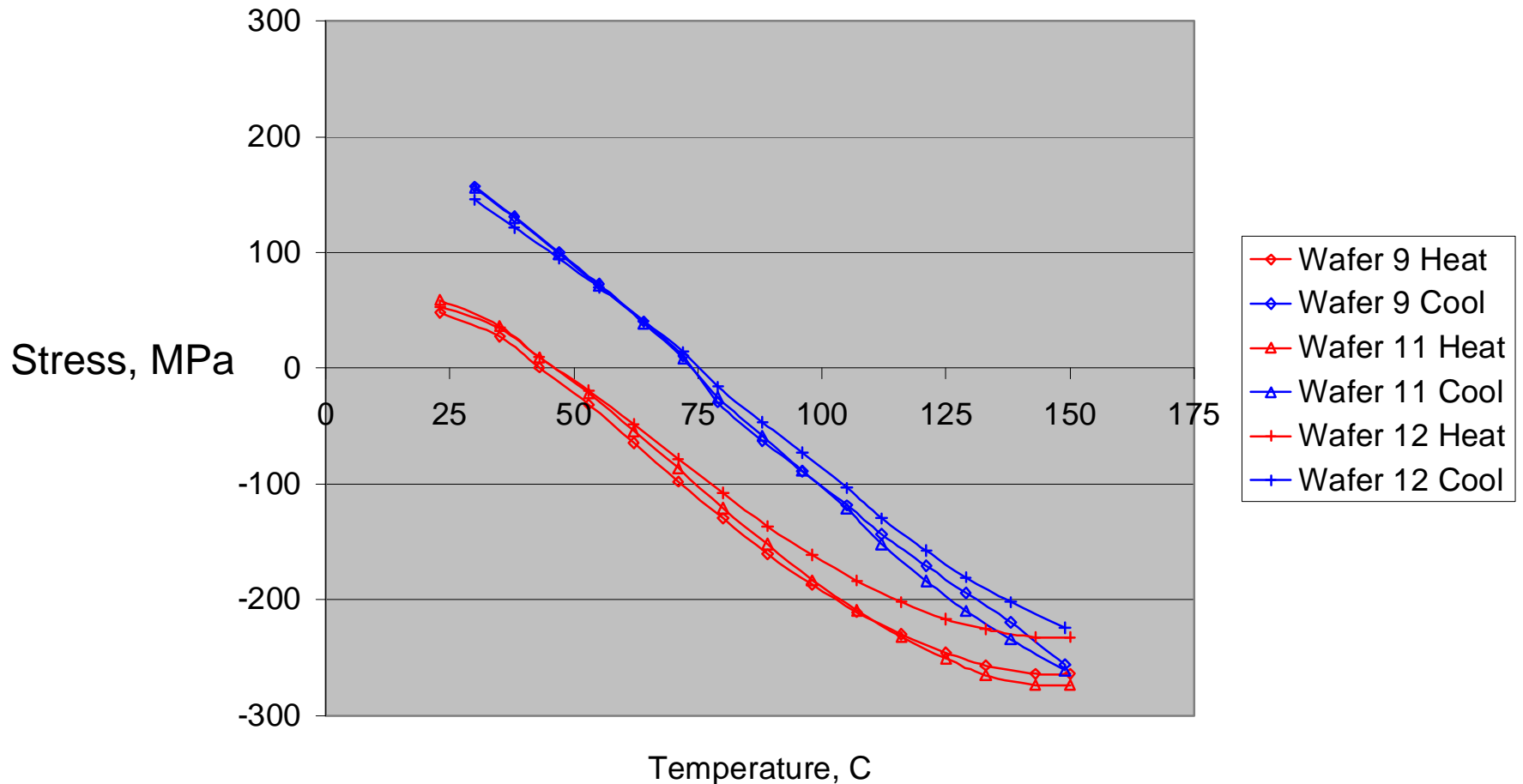


Fraunhofer IOF



# Problem: Thermal budget affects material properties

- Thermal cycle caused 100MPa change in residual stress due to plastic deformation in metal film



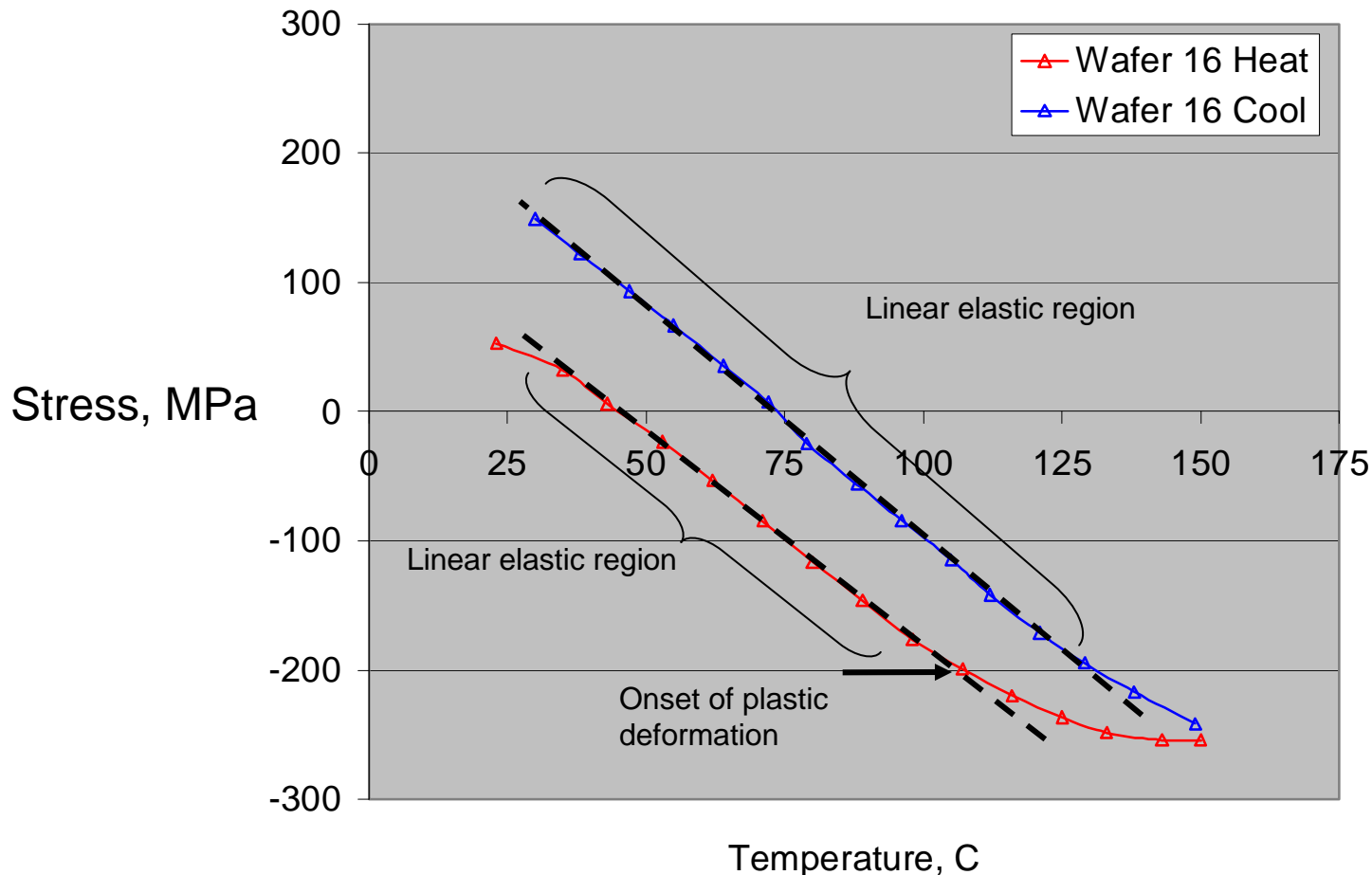
# Solutions: Parameter sensitivity analysis

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- **Conduct Design of Experiments in the computer, not the fab! Many permutations can be quickly evaluated.**
  - Start with textbook material property values
  - Hold modulus (E) constant, vary geometry
  - Hold geometry constant, vary E, etc.
  - Try to reduce sensitivity to material properties through smart design choices
- **If your design is sensitive to material properties, you will need measurements to improve simulation accuracy**
  - Wafer-level
  - Test structures

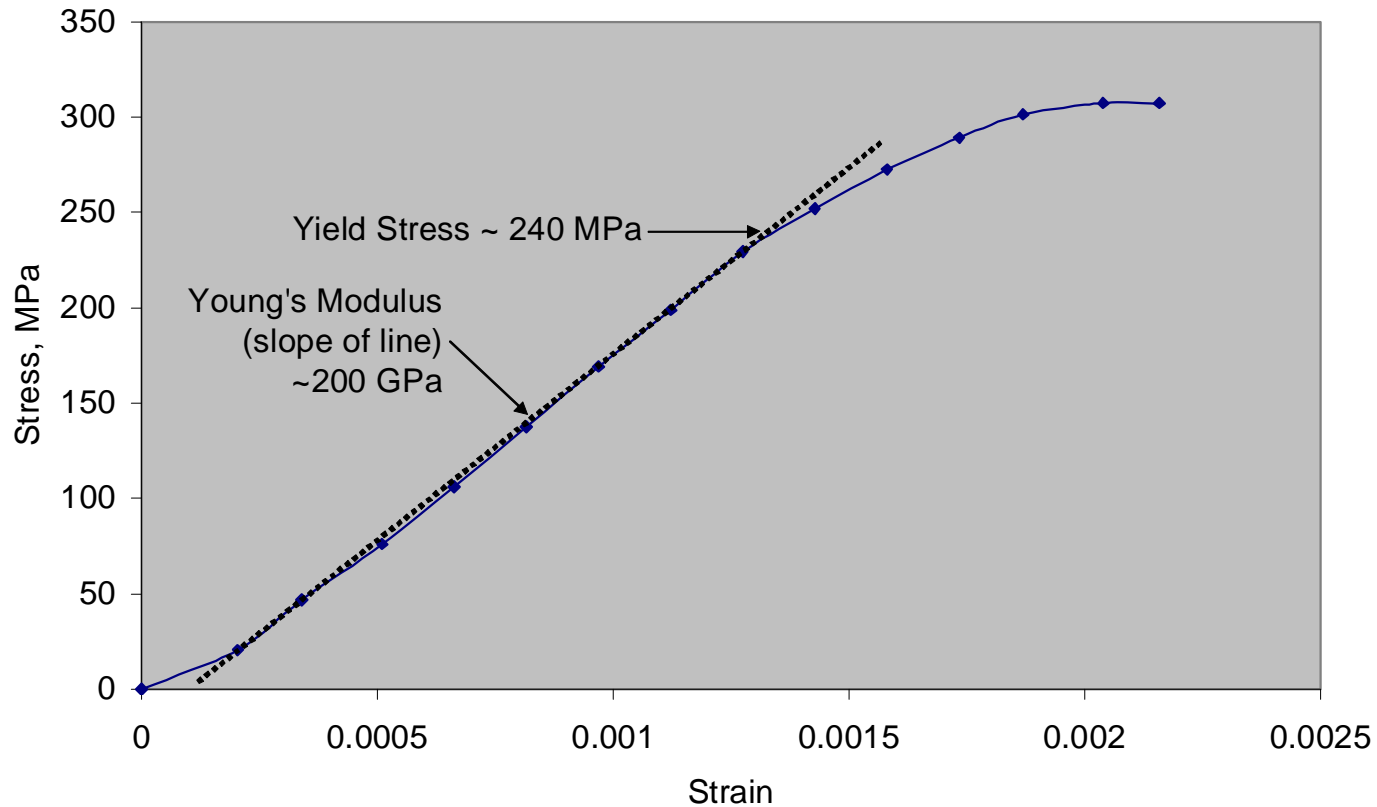
# Solutions: Wafer-level measurements

- KLA-Tencor Flexus scans on whole wafers with blanket films can provide a lot of useful data



# Solutions: Wafer-level measurements

- Modulus  $E$ ,  $\sigma_{\text{yield}}$  can be estimated from wafer-level film stress data

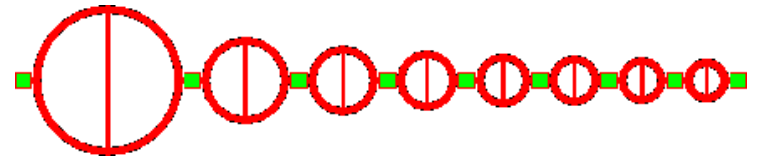


$$\varepsilon = \alpha \Delta T$$

# Solutions: Test Structures

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- **Strive for simple test structures that can be made with a subset of the process flow**
  - Cantilevers, Guckel rings, etc.



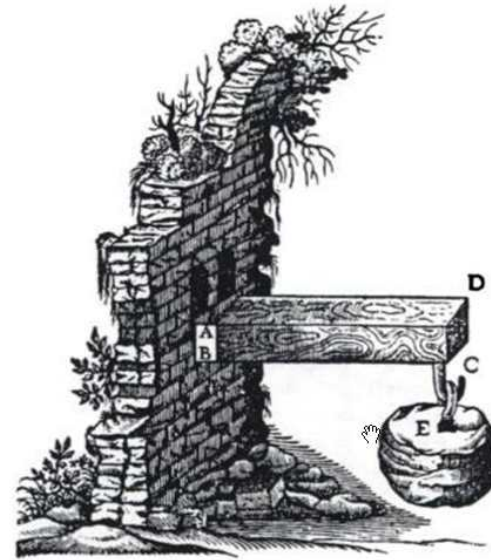
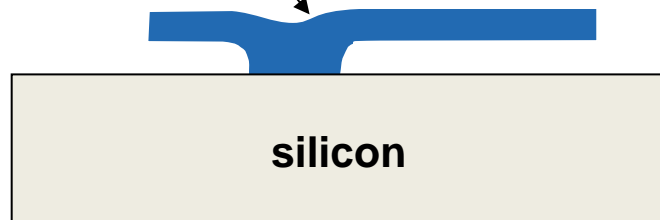
Visual indicator of stress

- **Resources for test structures and techniques:**
  - NIST: <http://www.eeel.nist.gov/812/test-structures/MEMSCalculator.htm>
  - MUMPS: <http://www.memscapinc.com/cug/mc6.html#3.3.3>
- **NIST and ASTM standards for thin film testing:**
  - E 2244, 2245, 2246: Measurements of Thin, Reflecting Films Using an Optical Interferometer

# Problem: Accurate model boundary conditions

- “Fixed” condition usually too stiff compared to reality
- Thin film structures do not have true “built-in” conditions

Polysilicon cantilever or membrane

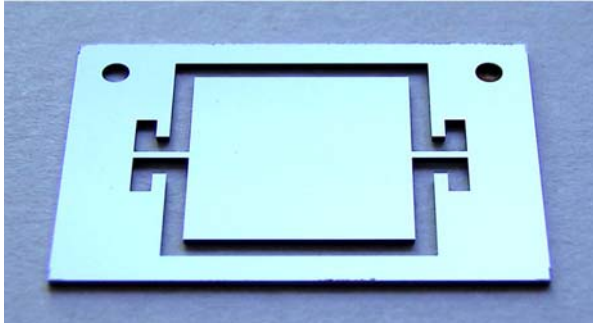


Fixed condition: Galileo's model of the built-in cantilever

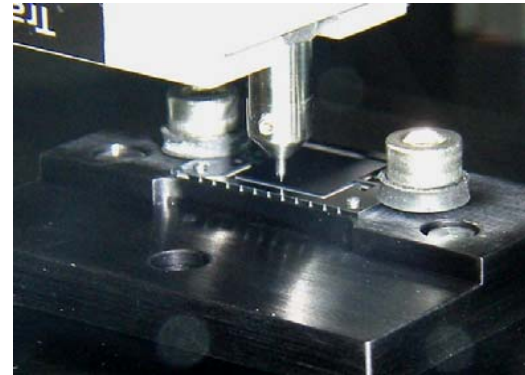
J.W. Wittwer, L.L. Howell, “Mitigating the Effects of Local Flexibility at the Built-In Ends of Cantilever Beams”, Journal of Applied Mechanics, Volume 71, Issue 5, pp. 748-751 (2004)

# Solution: Measure stiffness to correct model

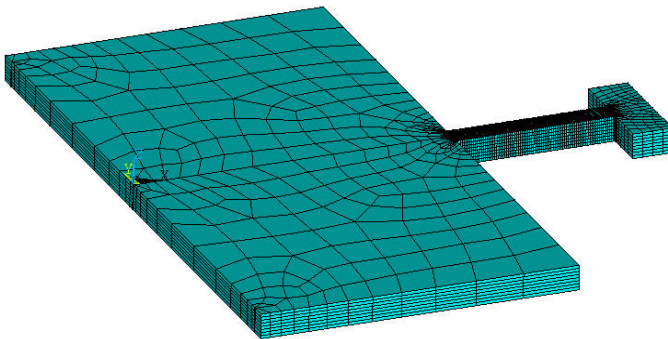
Simple micro-mirror



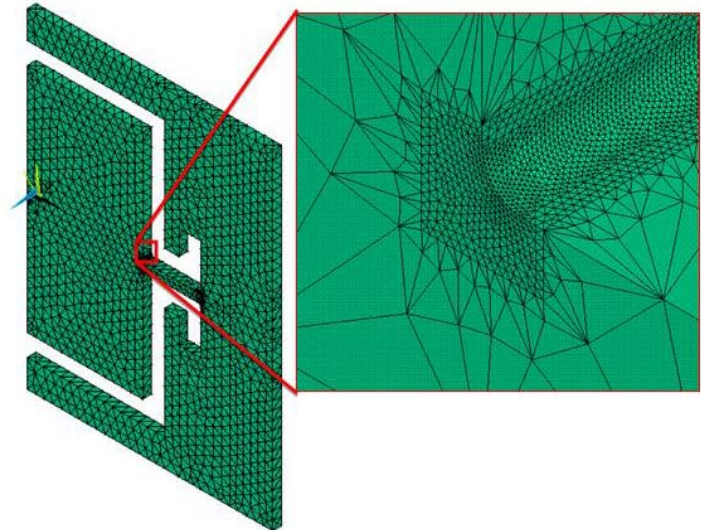
Force vs. displacement measurements proved original model too stiff!



Original FE half-model

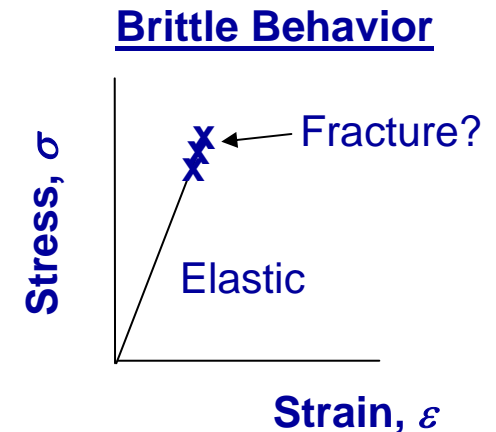
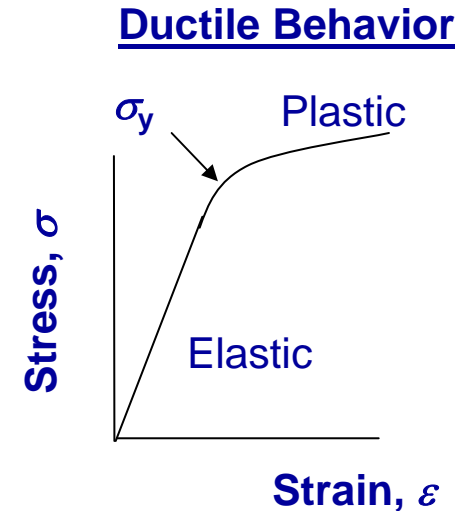


Improved half-model



# Problem: Predicting load limit of a brittle structure

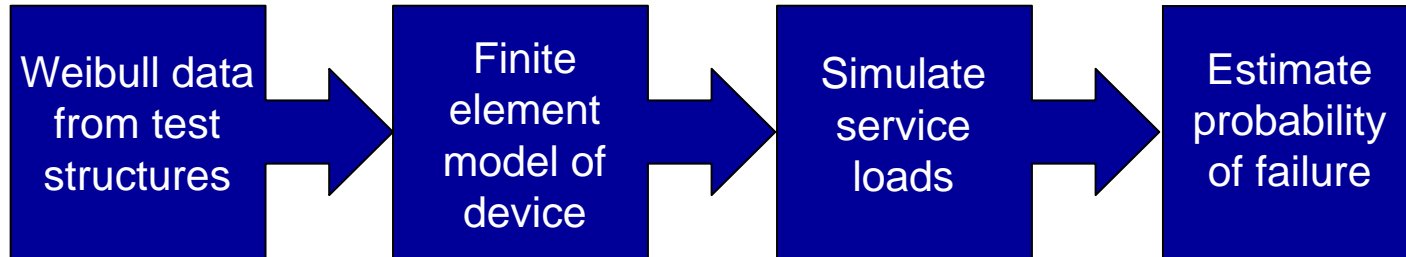
- **Ductile materials (metals) fail at yield strength**
  - Well-defined limit
  - Safety factor analysis
- **Brittle materials (silicon, glass) have a fracture toughness**
  - Strength is a function of flaw distribution (size, location)
  - Etching creates surface flaws!
- **MEMS structural reliability depends on etched surface properties**





## Solution: Integrate test data with simulation

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- **Break test structures to determine fracture stress distribution of each machined surface**
  - Use Weibull statistics
  - Once process is characterized, use data to analyze any MEMS device made by that process
- **AMFitzgerald proprietary algorithm to predict fracture risk of a complex device *without having to build or break it***

## Closing remarks

# How to do more efficient MEMS development

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- **Acquire a simulation tool AND an engineer skilled in modeling**
  - You'll save at least one fab round per year, they'll pay for themselves
- **Invest in developing accurate models for your technology, future products will benefit**
  - Simple tests can harvest important materials data
- **Practice good engineering discipline – fight the urge to “just build it”**
  - The fab is expensive, simulation is not!

# How to help the MEMS industry mature

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- **Give your EDA provider feedback on your simulation needs**
- **Motivate your foundry to provide characterized processes and materials property data**
- **Find ways to share data and insights without compromising confidentiality**
- **Participate in standards committees**

# How we can help you with MEMS development

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- **Expert design and simulation help**
- **Material properties data acquisition**
  - Test structure design
  - Measurement methods: wafer and die-level
  - Mechanical testing
  - Custom test apparatus
- **MEMS prototyping**
- **Foundry selection and transfer**



We use an Instron 5942 for mechanical testing



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